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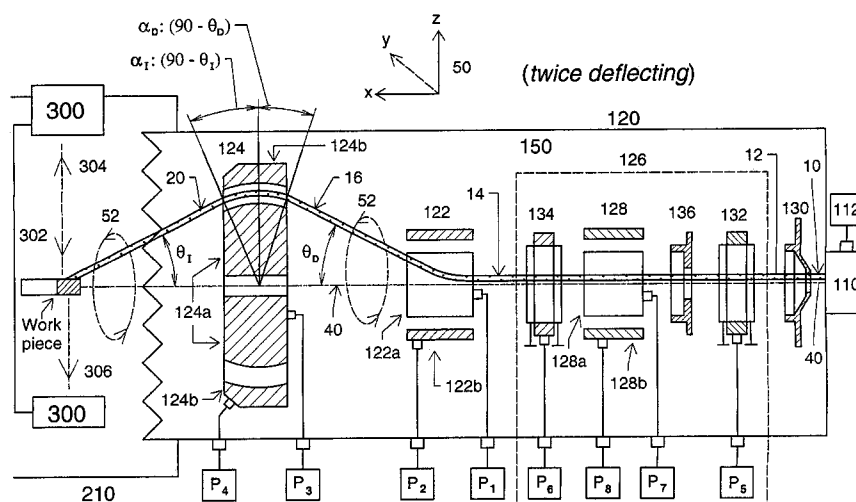
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(54) Title: DIRECTED MULTI-DEFLECTED ION BEAM MILLING OF A WORK PIECE AND DETERMINING AND CONTROLLING EXTENT THEREOF



(57) Abstract: Method, device, and system, for directed multi-deflected ion beam milling of a work piece, and, determining and controlling extent thereof. Providing an ion beam (10); and directing and at least twice deflecting the provided ion beam, for forming a directed multi deflected ion beam, wherein the directed multi-deflected ion beam is directed towards, incident and impinges upon, and mills, a surface of the work piece. Device includes an ion beam source assembly (110); and an ion beam directing and multi-deflecting assembly (120), for directing and at least twice deflecting the provided ion beam, for forming a directed multi-deflected ion beam, wherein the directed multi-deflected ion beam is directed towards, incident and impinges upon, and mills, a surface of the work piece.

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